



This project has received funding from the ECSEL Joint Undertaking under grant agreement No 737465. This Joint Undertaking receives support from the European Union's Horizon 2020 research and innovation programme and Germany, Belgium, Ireland.

MICROPRINCE:

Open access pilot line for Micro-Transfer-Printing of functional components on wafer level

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X-Celeprint US/ Ireland

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- 2) Motivation for Micro-Transfer-Printing (μ TP)
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1) MICROPRINCE- Funded project for μ TP

- MICROPRINCE is funded by **ECSEL JU** within the HORIZON 2020 call. 

ECSEL Joint Undertaking
Electronic Components and Systems for European Leadership
- The project is focused on creating the worldwide first open access **pilot line for heterogeneous integration** of smart systems by **micro-transfer-printing (μ TP)** in a semiconductor foundry manufacturing environment.
- The project duration is planned with 3 years (04/2017-03/2020).
- Consortium consists of **13 partners** from industry and research.



• MEMS Foundry GmbH
• Semiconductor Foundry GmbH
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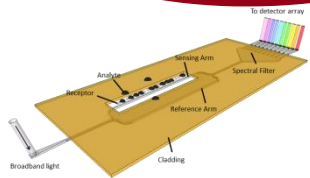


- Melexis Technologies
- Melexis Technologies SA
- Melexis NV
- Melexis GmbH

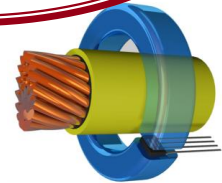
1) Introduction of the funded project

- Project goals:

Devices for Si-photonics



Printed GaAs Hall plates



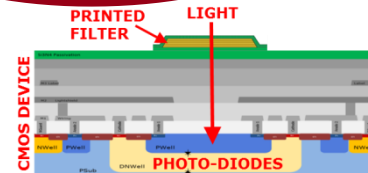
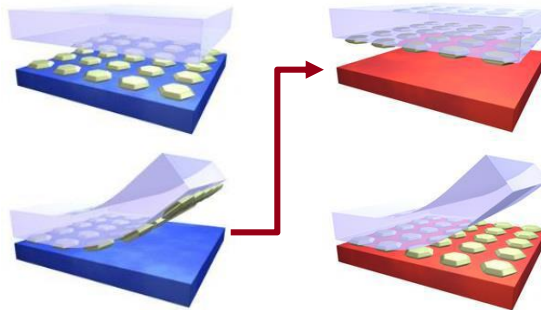
Installation of a μ TP Pilot line for an open access platform



Printed optical filters



Printing LEDs



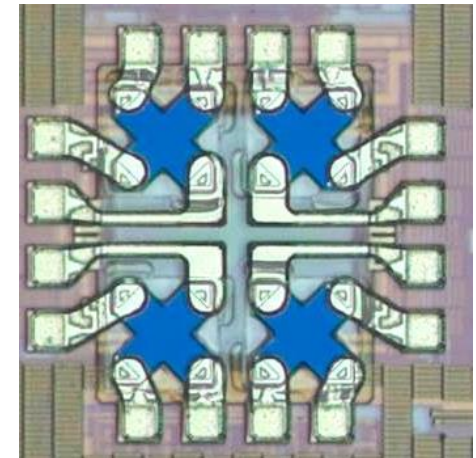
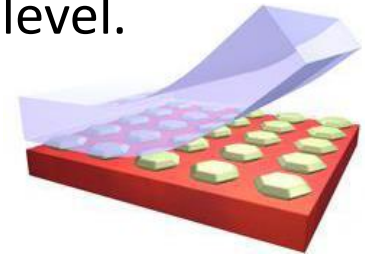
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2) Motivation for μ TP



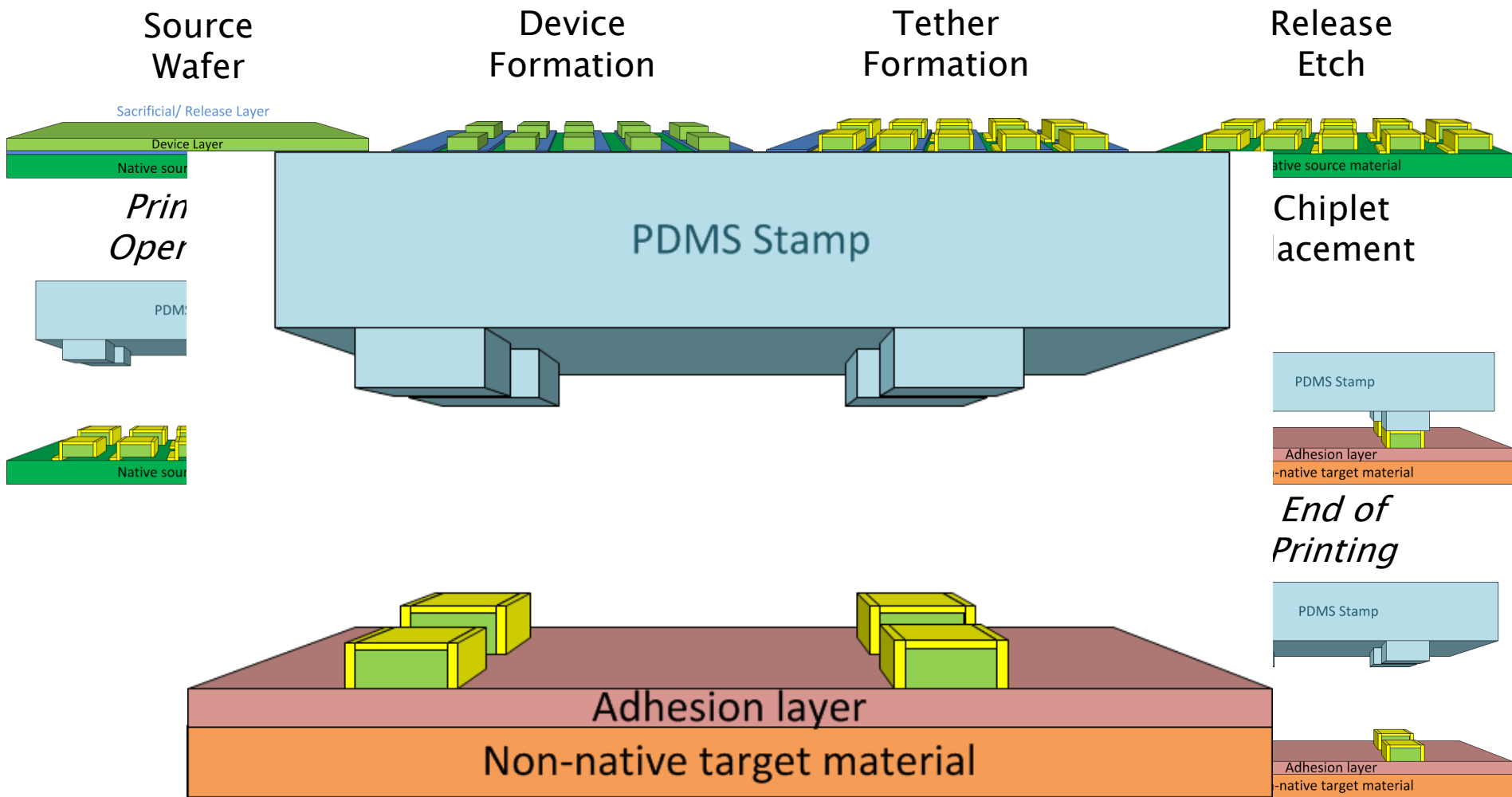
- Technology for **heterogeneous integration** on wafer level.
- Pronounced potential for **parallel placement**.
- High **placement accuracy** is achievable $\rightarrow \pm 1.5\mu\text{m}$ (3σ).
- Very **short metallization tracks** accessible \rightarrow low impedance.
- Reduced package sizes accessible.
- Transfer/ packaging of **small & thin devices**.
 - Height of down to $2\text{-}3\mu\text{m}$.
 - Lateral dimensions below $50 \times 50\mu\text{m}^2$ possible.
- Placement in small cavities achievable.
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3. General μ TP process- Printing



3. General μ TP process- Printing

Source Wafer

Device Formation

Tether Formation

Release Etch

Sacrificial/ Release Layer

Device Layer

Native source material

Native source material

Native source material

Native source material

Printing Operation

Chiplet Picking

Chiplet Transfer

Chiplet Placement

PDMS Stamp

PDMS Stamp

PDMS Stamp

PDMS Stamp

Native source material

Native source material

Native source material

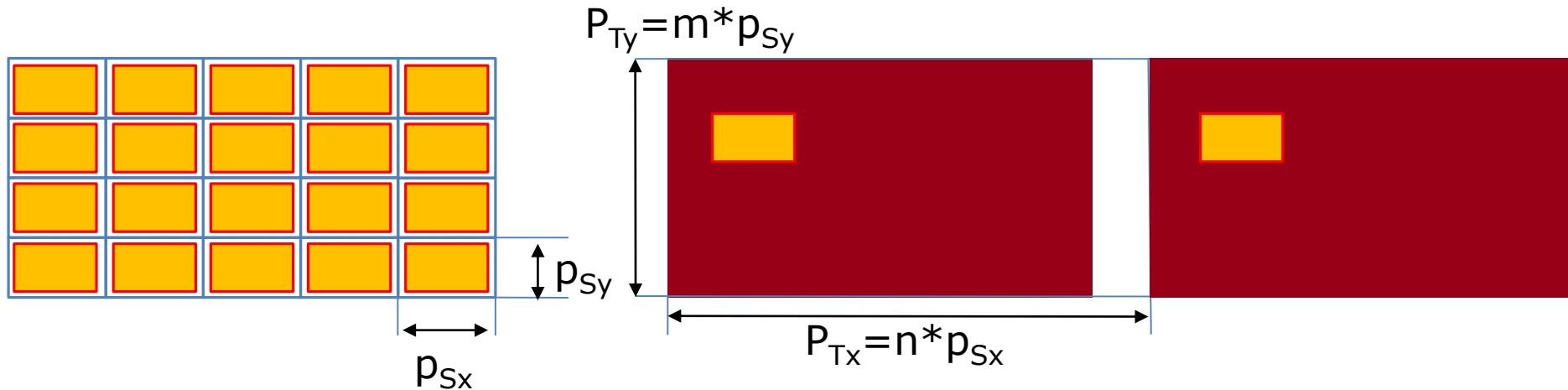
Adhesion layer
Non-native target material

End of Printing

PDMS Stamp

Adhesion layer
Non-native target material

3. General μ TP process- Design restrictions

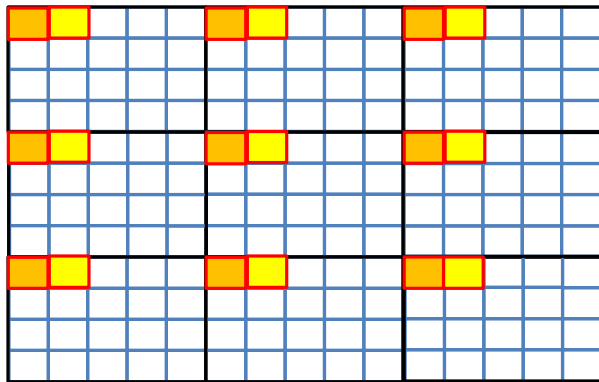


- Correlation between target and source die pitches are required:

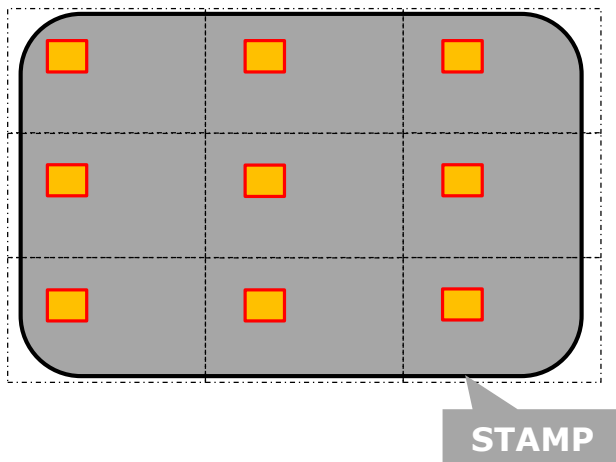
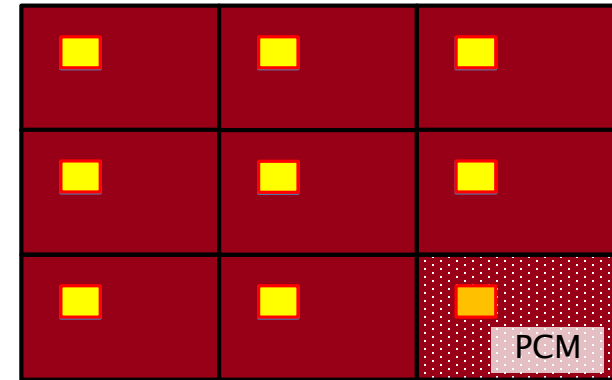
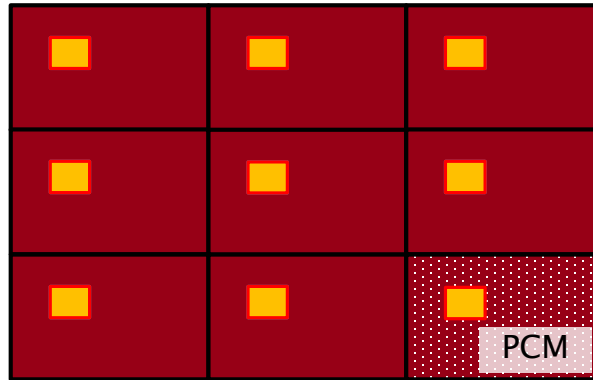
$$P_{Tx} = n \cdot p_{Sx} \text{ \& } P_{Ty} = m \cdot p_{Sy}$$

- **Target die pitches** must be **multiples of the source die pitches**.
- m, n are integer.
- Target chip grid includes dicing lines, source chip grid includes area for tethers and anchor structures.

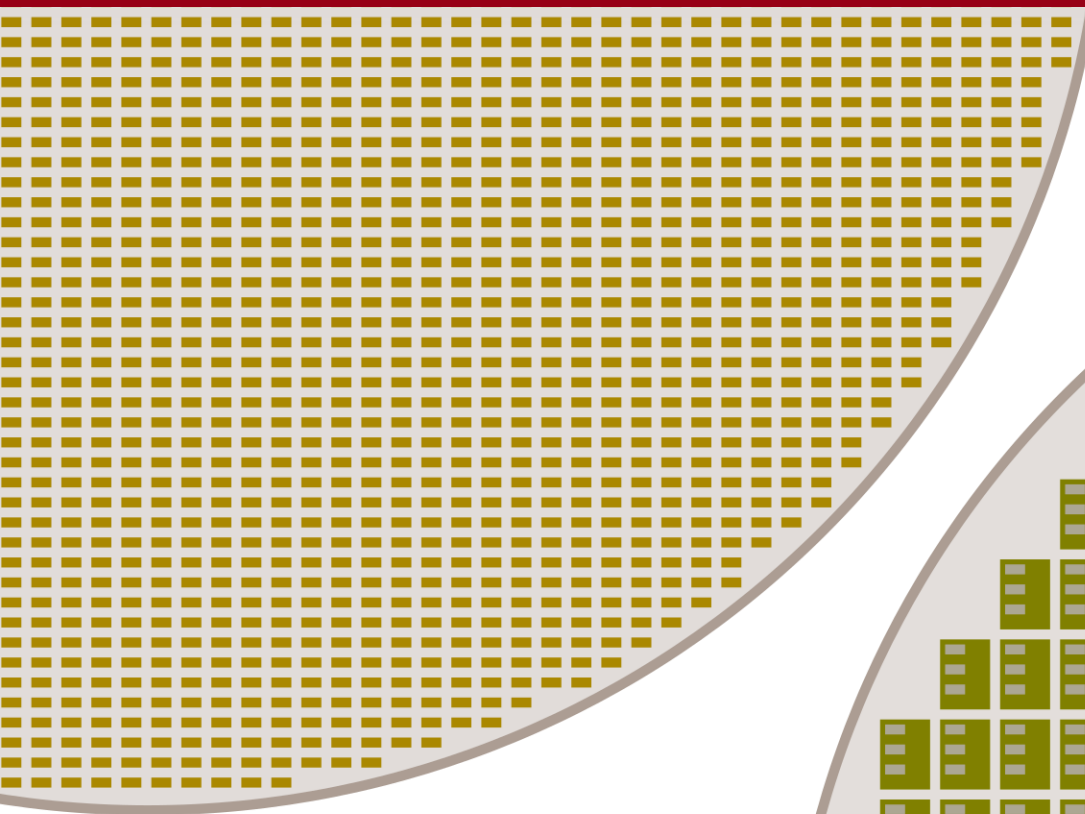
3. General μ TP process- Design restrictions



Printfield Source wafer

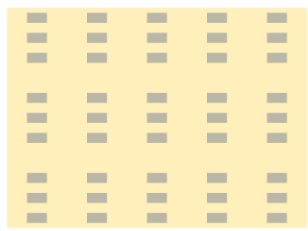
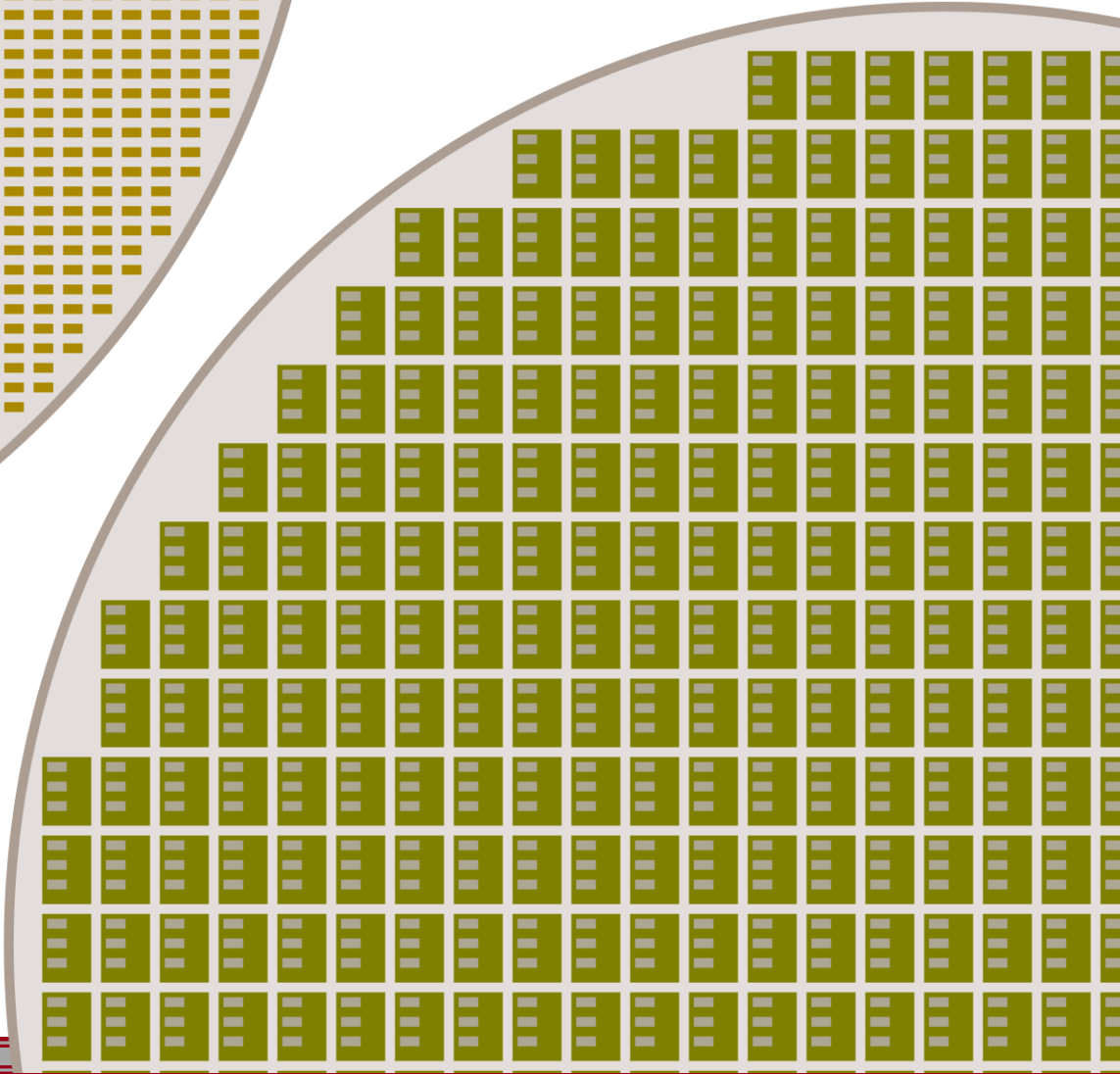


- Requirements of array printing:
 - Stamp populates equivalent areas along the wafer.
 - PCM layout is pre-defined by chip design → one chip per reticle PCM test fields .
 - PCM test has to be designed individually per application.

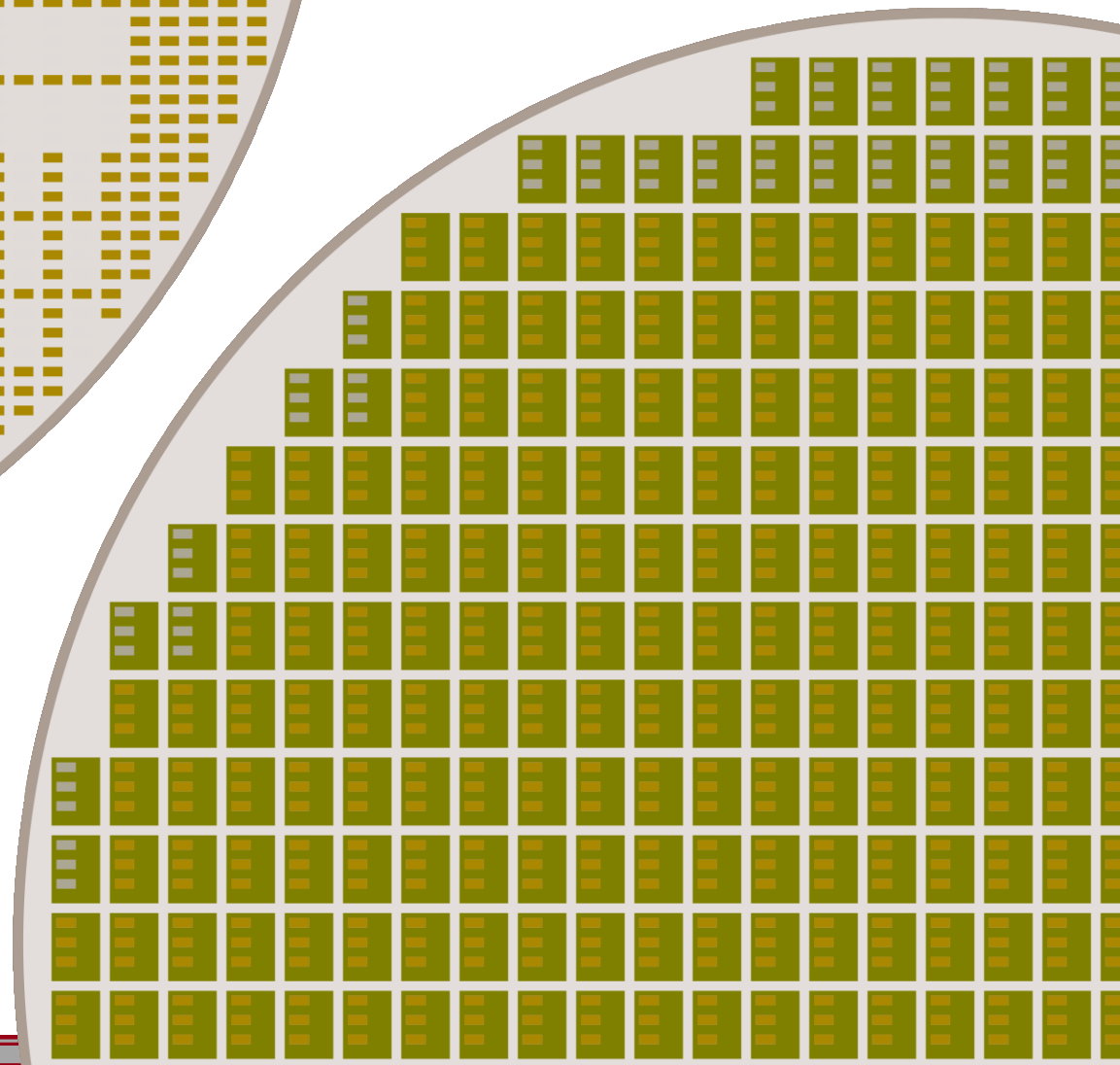
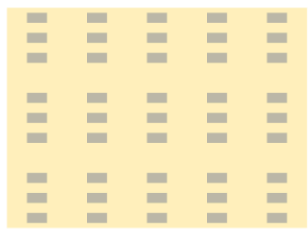
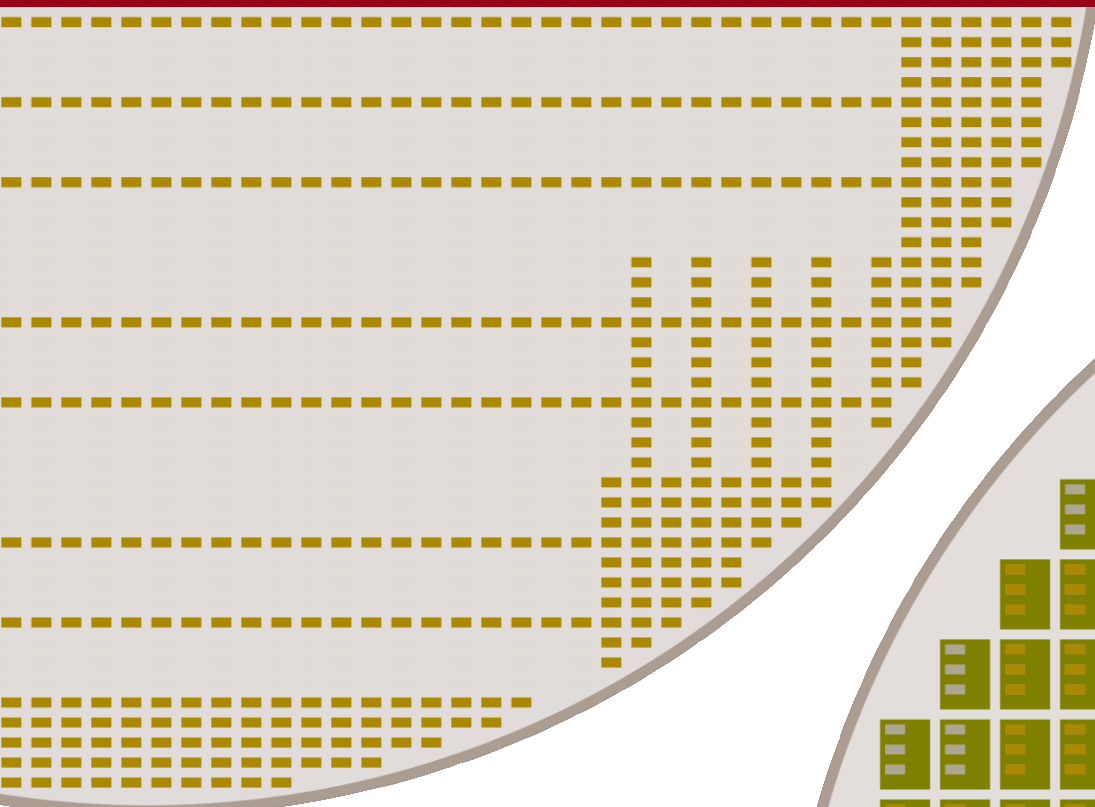


Source wafer

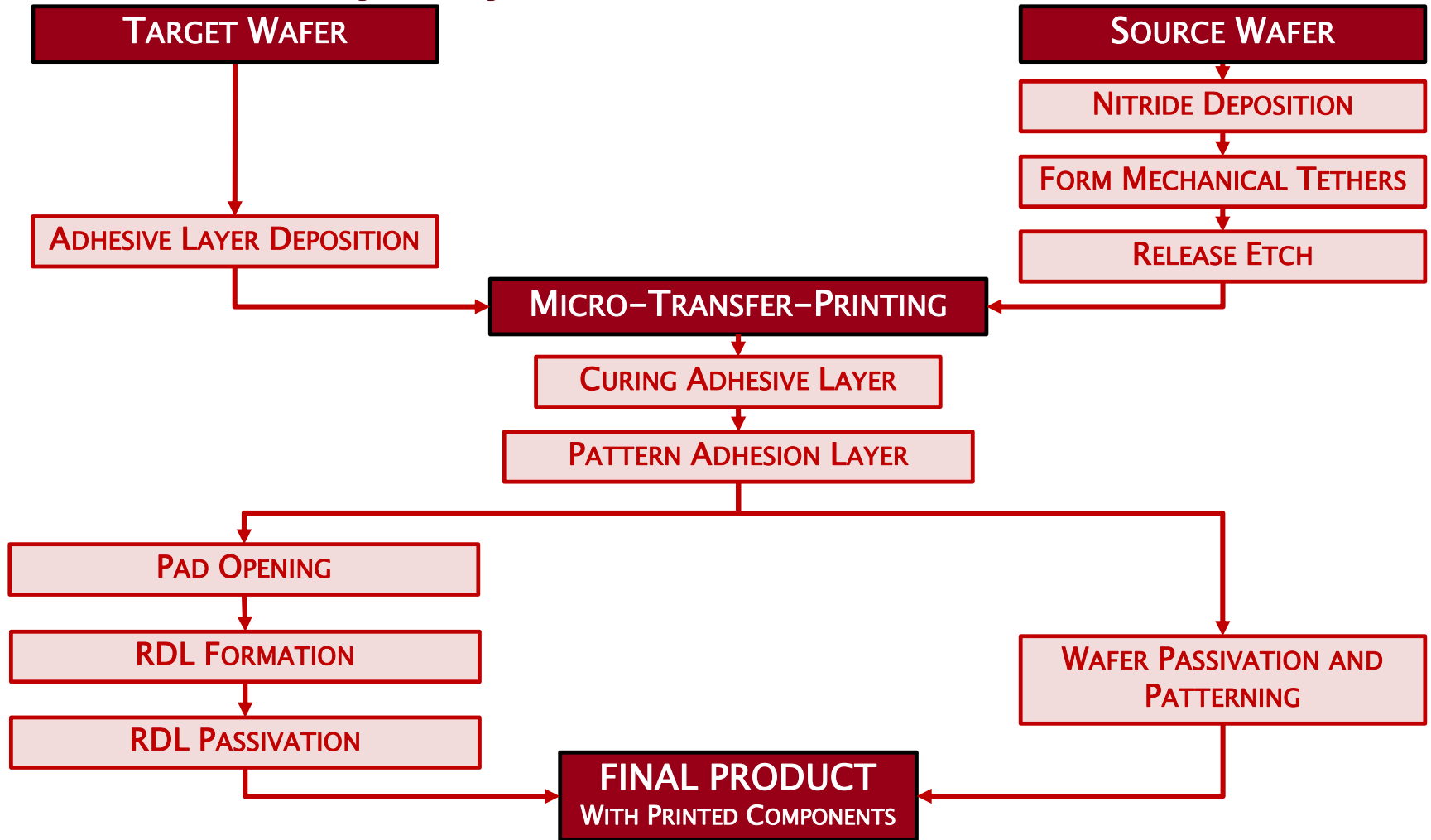
Target wafer



Stamp



3. General μ TP process- Flow Chart

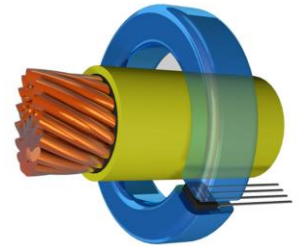


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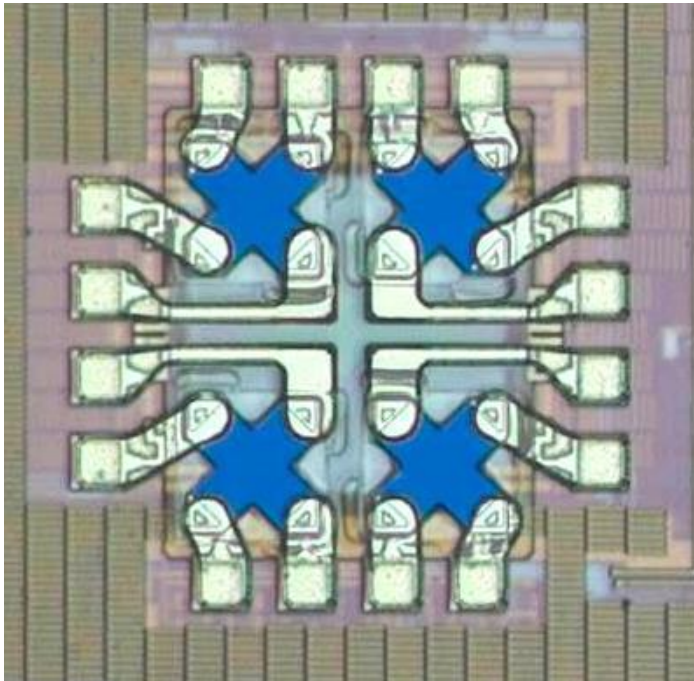
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4) Target applications- GaAs Hall Plates

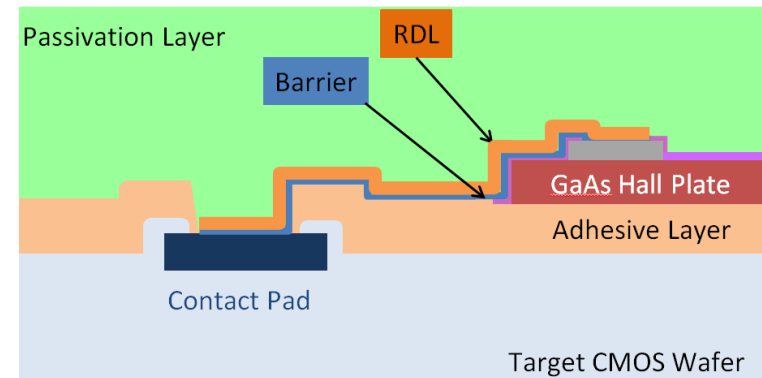
Melexis



- μ TP for highly sensitive magnetic sensors.

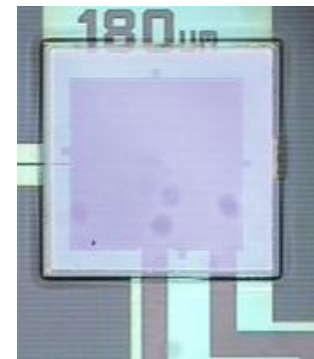


- Integration of GaAs Hall plates shall overcome the limitations of Si devices.
- GaAs offers a higher electron mobility and allows therefore a higher sensitivity to magnetic fields.

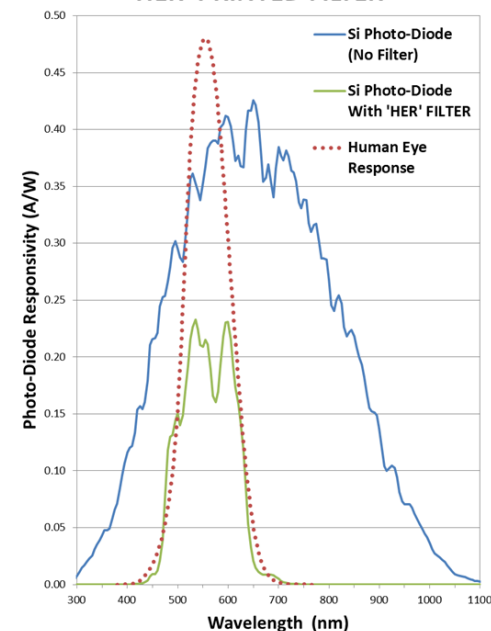
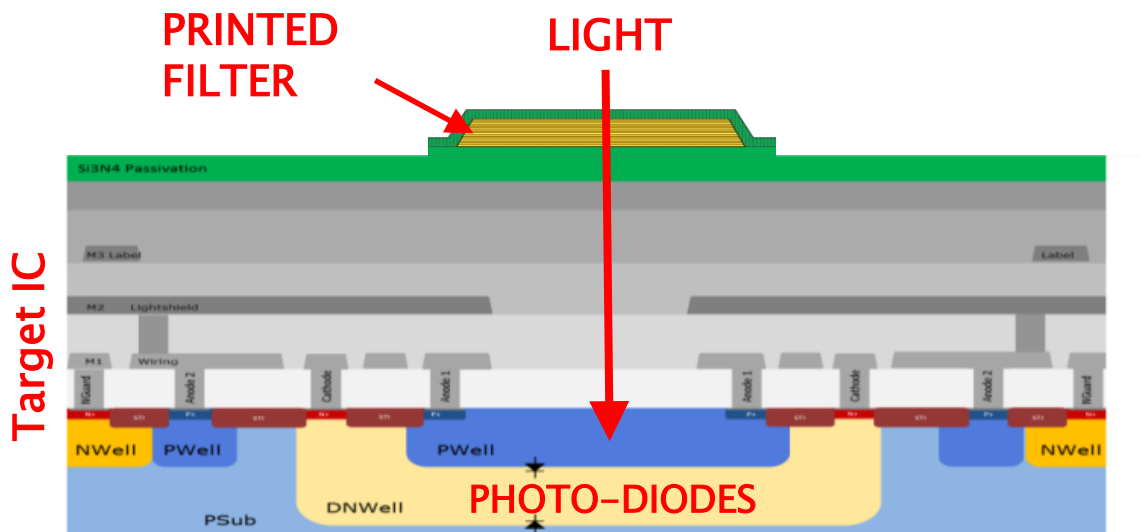


4) Target applications- Printed Filter

- μ TP of filters for Human Eye Response sensors.
- More efficient utilization of expensive filter material.
- Furthermore, μ TP could be applied for the integration of different filter materials on one chip.



'HER' PRINTED FILTER

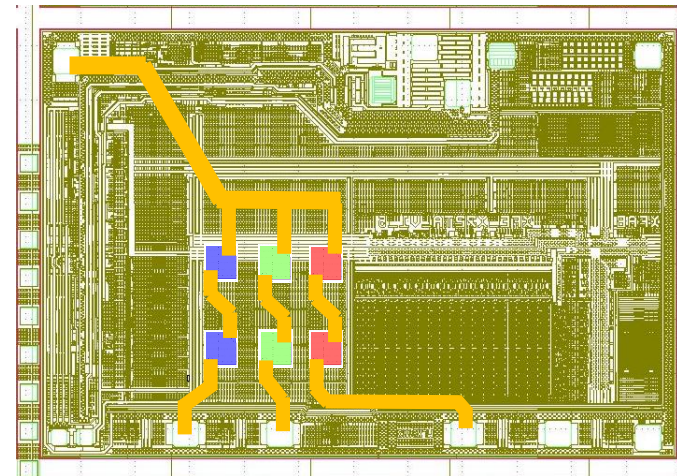
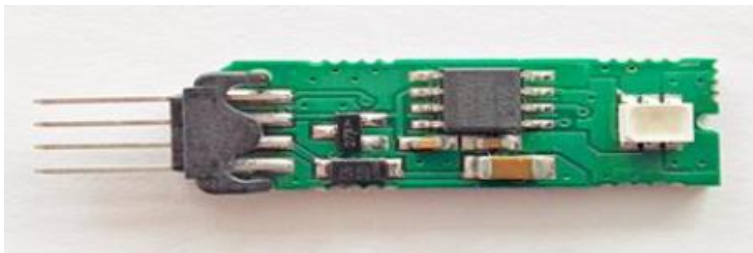


4) Target applications- LEDs for ambient lighting

- Transfer printing of RGB μ LEDs for ambient lighting in cars.



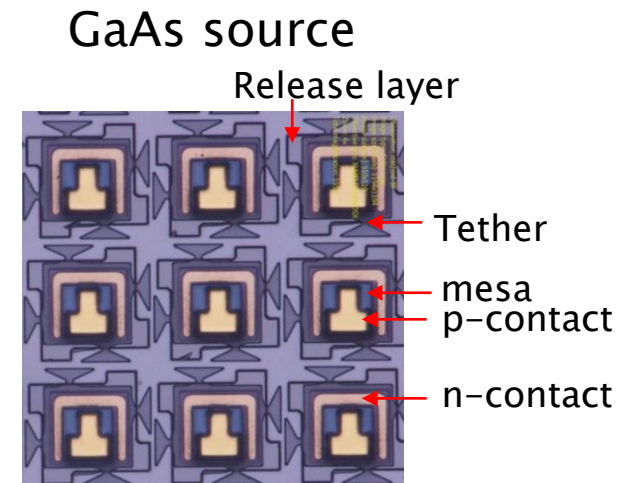
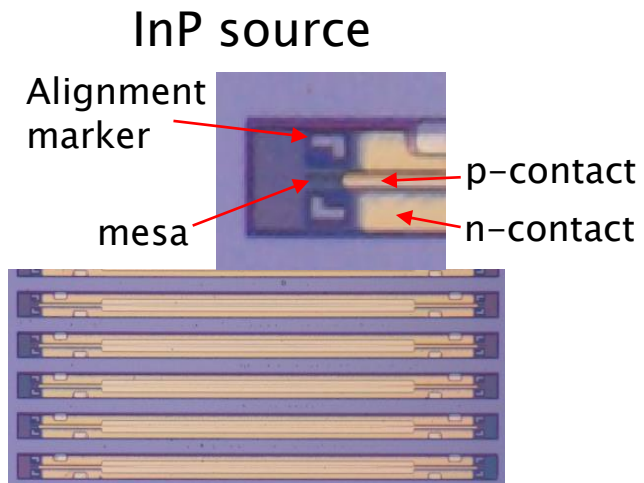
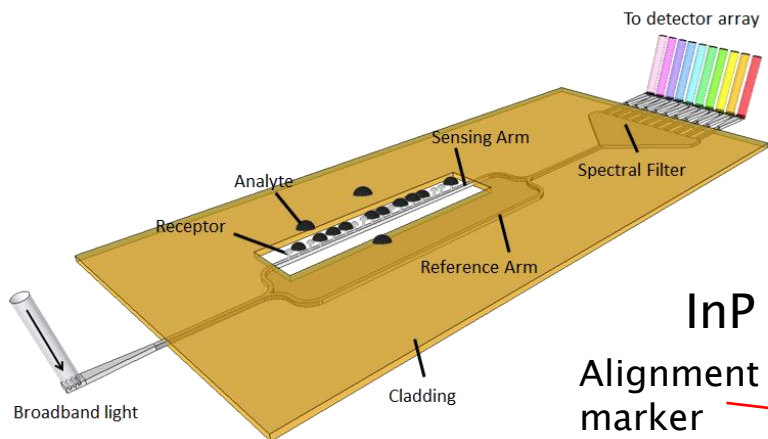
- By printing directly on the driver IC: cost efficient, more flexible and smaller packages shall be achieved.
- Special requirements on LED design.



4) Target applications- Si-Photonic devices



- Transfer printing of III/V active devices for Si-photonics biomedical application.
- Cost efficient setup of spectroscopic sensing applications by including GaAs & InP photodiodes and LEDs in passive Si & SiN photonic circuits.



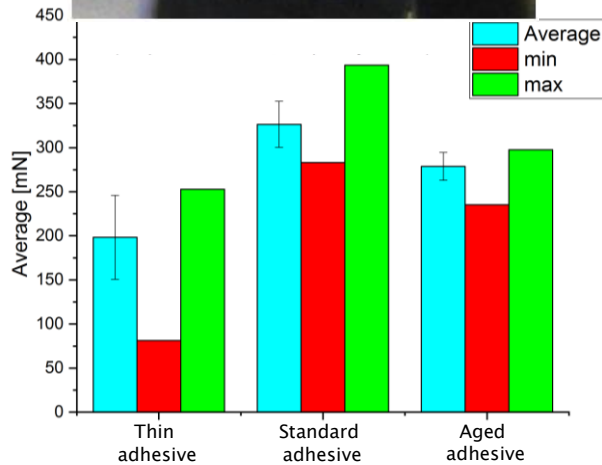
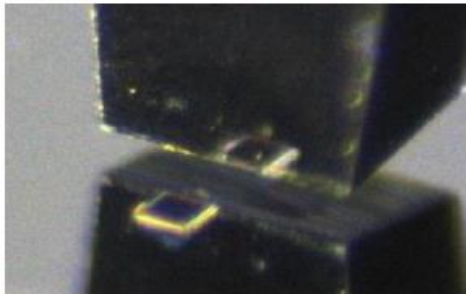
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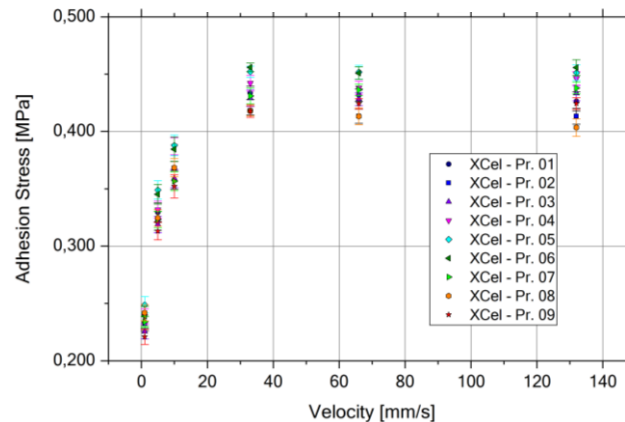
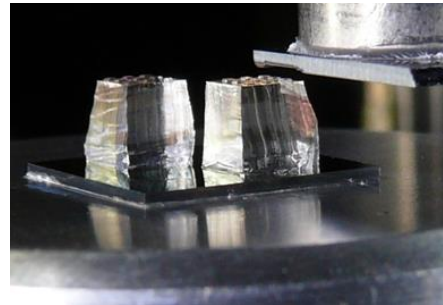
5) Process characterization

- Various process and device characterizations as well as simulation are performed:

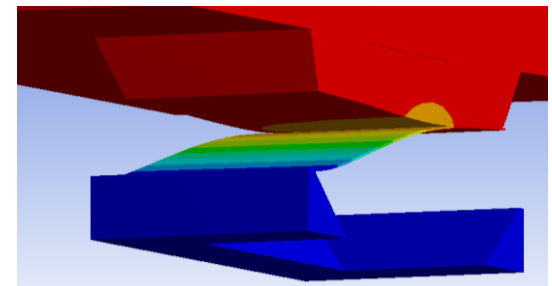
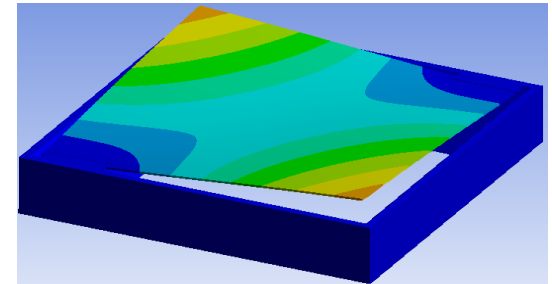
Adhesion tests



Stamp characterization



FEA Modeling

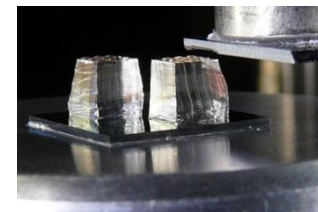
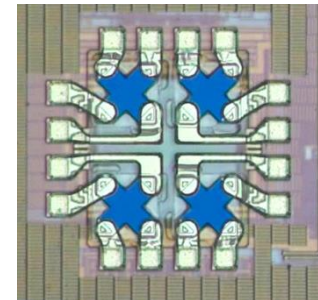
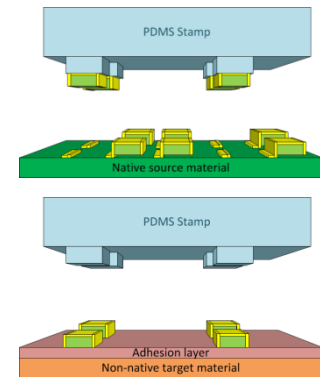


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6) Summary

- The MICROPRINCE project aims on the **installation of a pilot line for Micro-Transfer-Printing (μ TP)**.
- μ TP is a versatile technology for **parallel heterogeneous integration on wafer level**.
- Within the project the capabilities of this technology will be demonstrated for several target applications: **GaAs Hall Plates, filters, LEDs and Si-photonics**.
- Furthermore, the process and material characteristics are extensively investigated within the project.



Aknowledgement

- "The **Microprince** project has received funding from the European Union's H2020 Programme (ECSEL JU) under grant agreement number 737465"



- Thanks to all the project partners and involved team members for their contribution, the provided data and the collaboration.



- MEMS Foundry GmbH
- Semiconductor Foundry GmbH

supported by
TECHNIKON



University College Cork, Ireland
Coláiste na hOllscoile Corcaigh



- Melexis Technologies
- Melexis Technologies SA
- Melexis NV
- Melexis GmbH

Thank you for your kind attention.

MICROPRINCE- Goals

- Transfer of the μ TP-technology for microelectronics application from **research to an industrial environment.**
- **Creation, installation and demonstration of a μ TP pilot line** in a manufacturing environment for open access.
- Technology demonstration for **five defined target applications:** Hall plates for **current sensors**; filter for **optical sensors**; μ LEDs for **car ambient lighting**; LEDs, sensors and modulators for **communication** and **bio-medical Si-photonics** applications.
- Realization of printing processes from and on different wafer sizes (3, 4, 6 & 8 inch) mm silicon wafers.
- Development of μ TP as platform technology including **design rules** and their implementation in **Process Design Kits (PDK).**

MICROPRINCE- Project structure

WP 8: Project- and Innovation Management

WP7: Dissemination, Communication, Exploitation and Standardization (Lead: IMWS)

WP2:
Micro-Transfer-
Printing for High
Sensitivity
Magnetic
Sensors

(Lead: MLX TLO)

WP3:
Micro-Transfer-
Printing for
Optical Sensors

(Lead: XFAB)

WP4:
Micro-Transfer-
Printing for
Silicon Photonics

(Lead: HUA)

WP5:
Micro-Transfer-
Printing of LED
Devices

(Lead: MLX DE)

WP6:
Micro-Transfer-
Printing for
Biomedical
Implant
Applications

(Lead: IMEC)

WP1: Design and installation of the μ TP pilot line (Lead: XMF)

- Specification, set-up and installation of the pilot line for high volume production in a MEMS foundry environment
- Development and providing of general process for manufacturing

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